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Title of Invention	Method of Forming Silicon Dioxide Using Siloxane	
Application Number :	10/782094	
Date :	2005-01-03	
First Named Applicant:	Mr. Park Jae-Eun	
Confirmation Number:	4756	
Attorney Docket Number:	SAM-0483	
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Mr. Anthony P. Onello Jr. Registered Number: 38,572	/Anthony P. Onello, Jr./	Attorney

Documents being submitted:	Files
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Comments	
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